

ABSTRACT OF THE DISCLOSURE**A DIAMOND GRID CMP PAD DRESSER**

The present invention discloses a CMP pad dresser which has a plurality of uniformly spaced abrasive particles (180) protruding therefrom. The abrasive particles (180) are super hard materials, and are typically diamond, polycrystalline diamond (PCD), cubic boron nitride (cBN), or polycrystalline cubic boron nitride (PcBN). The abrasive particles (180) are attached to a substrate (40) which may be then coated with an additional anti-corrosive layer (130). The anti-corrosive layer (130) is usually a diamond or diamond-like carbon which is coated over the surface of the disk to prevent erosion of the brazing alloy (90) by the chemical slurry used in conjunction with the CMP pad. This immunity to chemical attack allows the CMP pad dresser to dress the pad while it is polishing a workpiece. In addition to even spacing on the substrate (40), the abrasive particles (180) extend for a uniform distance away from the substrate (40), allowing for even grooming or dressing of a CMP pad both in vertical and horizontal directions. A method of producing such a CMP pad dresser is also disclosed.

"
Fig. 3